

Kristina Johansson

List of Publications by Year in descending order

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11
papers

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| # | ARTICLE | IF | CITATIONS |
|----|---|-----|-----------|
| 1 | Multicomponent Hf-Nb-Ti-V-Zr nitride coatings by reactive magnetron sputter deposition. <i>Surface and Coatings Technology</i> , 2018, 349, 529-539. | 4.8 | 58 |
| 2 | Multi-component (Al,Cr,Nb,Y,Zr)N thin films by reactive magnetron sputter deposition for increased hardness and corrosion resistance. <i>Thin Solid Films</i> , 2020, 693, 137685. | 1.8 | 41 |
| 3 | Optimizing the stoichiometry of ultrathin NbTiN films for high-performance superconducting nanowire single-photon detectors. <i>Optics Express</i> , 2019, 27, 26579. | 3.4 | 36 |
| 4 | Influence of Deposition Temperature on the Phase Evolution of HfNbTiVZr High-Entropy Thin Films. <i>Materials</i> , 2019, 12, 587. | 2.9 | 31 |
| 5 | Influence of N content on structure and mechanical properties of multi-component Al-Cr-Nb-Y-Zr based thin films by reactive magnetron sputtering. <i>Surface and Coatings Technology</i> , 2020, 389, 125614. | 4.8 | 31 |
| 6 | Experimental and theoretical evidence of charge transfer in multi-component alloys – how chemical interactions reduce atomic size mismatch. <i>Materials Chemistry Frontiers</i> , 2021, 5, 5746-5759. | 5.9 | 14 |
| 7 | Corrosion properties of CVD grown Ti(C,N) coatings in 3.5 wt-% NaCl environment. <i>Corrosion Engineering Science and Technology</i> , 2018, 53, 316-320. | 1.4 | 11 |
| 8 | Influence of oxygen content on structure and material properties of reactively sputtered Al-Ge-O-N thin films. <i>Journal of Alloys and Compounds</i> , 2018, 738, 515-527. | 5.5 | 10 |
| 9 | Influence of the nitrogen content on the corrosion resistances of multicomponent AlCrNbYZrN coatings. <i>Corrosion Science</i> , 2021, 188, 109557. | 6.6 | 9 |
| 10 | Optical and electrical properties of hard (Hf,Nb,Ti,V,Zr)N _x thin films. <i>Vacuum</i> , 2021, 193, 110517. | 3.5 | 4 |
| 11 | In Situ Formation of Ge Nanoparticles by Annealing of Al-Ge-N Thin Films Followed by HAXPES and XRD. <i>Inorganic Chemistry</i> , 2019, 58, 11100-11109. | 4.0 | 2 |